

L Number	Hits	Search Text	DB	Time stamp
-	46	(photoresist or resist or mask\$4) same (dimethylsulfoxide or dimethyl\$1sulfoxide or dmso or "c.sub.2h.sub.6os") same etch\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/28 15:48
-	1	(photoresist or resist or mask\$4) same (dimethylsulfoxide or dimethyl\$1sulfoxide or dmso or "c.sub.2h.sub.6os") same etch\$4 same (grad\$3 or hplc)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/28 15:37
-	9	(photoresist or resist or mask\$4) same (dimethylsulfoxide or dimethyl\$1sulfoxide or dmso or "c.sub.2h.sub.6os") same (grad\$3 or hplc)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/28 15:38
-	1	(dimethylsulfoxide or dimethyl\$1sulfoxide or dmso or "c.sub.2h.sub.6os") near10 (HPLC or pressure near2 liquid adj chromatography) same etch\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/28 15:54
-	1	(dimethylsulfoxide or dimethyl\$1sulfoxide or dmso or "c.sub.2h.sub.6os") near10 (HPLC or pressure near2 liquid adj chromatography) same (photoresist or resist or mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/28 16:08